

PATENT

Attorney Docket No. 8003-370

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application )

PATENT APPLICATION

Inventor(s): Park et al. )

Art Unit: 1756

Application Serial No.: 09/624,712 )

Examiner: K. Duda

Filed: July 25, 2000 )

Title: Method For An Improved Developing Process)  
In Wafer Photolithography )AMENDMENTAssistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

Applicants submit this Amendment in response to the Office Action dated May 21, 2002. Reconsideration is respectfully requested in view of the following amendments and remarks.

In the Claims:

Please cancel claims 2-3, and amend claims 1 and 4 as follows:

(Amended) 1. A method for sequencing a developer process to reduce wafer pattern defects, comprising:

dispensing a substantially inert material onto a wafer surface to form a layer of substantially inert material prior to dispensing a developer fluid, wherein the substantially inert material is dispensed through a selected multi-dispense nozzle;

dispensing the developer fluid through the same multi-dispense nozzle onto the layer of inert material while spinning the wafer surface substantially

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